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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/044,178	01/10/2002	Todd Edgar	MIO 0011 N2	3193

7590 03/15/2005

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EXAMINER	
LE, THAO X	

ART UNIT	PAPER NUMBER
2814	

DATE MAILED: 03/15/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)	
	10/044,178	EDGAR, TODD	
	Examiner	Art Unit	
	Thao X. Le	2814	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1)☒ Responsive to communication(s) filed on *28 January 2005*.

2a)☐ This action is **FINAL**. 2b)☒ This action is non-final.

3)☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4)☒ Claim(s) *1-8* is/are pending in the application.

4a) Of the above claim(s) *6-8* is/are withdrawn from consideration.

5)☐ Claim(s) _____ is/are allowed.

6)☒ Claim(s) *1-5* is/are rejected.

7)☐ Claim(s) _____ is/are objected to.

8)☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9)☐ The specification is objected to by the Examiner.

10)☐ The drawing(s) filed on _____ is/are: a)☐ accepted or b)☐ objected to by the Examiner.

Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).

Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).

11)☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

12)☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

a)☐ All b)☐ Some * c)☐ None of:

1.☐ Certified copies of the priority documents have been received.

2.☐ Certified copies of the priority documents have been received in Application No. _____.

3.☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

1) ☒ Notice of References Cited (PTO-892)
2) ☐ Notice of Draftsperson's Patent Drawing Review (PTO-948)
3) ☐ Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date _____.
4) ☐ Interview Summary (PTO-413) Paper No(s)/Mail Date. _____.
5) ☐ Notice of Informal Patent Application (PTO-152)
6) ☐ Other: _____.

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

> A person shall be entitled to a patent unless –
>
> (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

2. Claims 1-5 are rejected under 35 U.S.C. 102(b) as being anticipated by US 5028990 to Kotaki et al.

Regarding claim 1, Kotaki discloses a storage container structure in fig. 10 comprising: a substrate 1, column 3 line 21, including a semiconductor structure; an insulating overlayer 6/8 disposed over and in contact with said substrate, insulating overlayer 6, column 4 line 25, including a container region 9 (groove), fig. 4b/9, disposed therein, said container region 9 defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by said container side walls and said container bottom wall; a patterning stop region 5b, column 3 line 23, fig. 10, disposed over said substrate 1 such that all of said container bottom wall is defined by an upper surface of said patterning stop region 5b, fig. 9; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region (where 16 is located) defined by said charge storage lamina, wherein said contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein said contact region side walls and

said contact region bottom wall are defined by a first surface of said charge storage lamina, fig. 10, and an electrical contact 16, column 4 line 68, in said contact region, wherein respective portions of said electrical contact 16 and said charge storage lamina 12/13/14 occupy collectively at least a portion of said container region.

Regarding claim 2, Kotaki discloses a storage container structure in fig. 10 comprising: a substrate 1 including a semiconductor structure; a patterning stop region 5B with a lower surface substantially coplanar with the top of said substrate1, fig. 10; an insulating overlayer 6 over said substrate, said insulating overlayer 6 comprising: a lower overlayer surface (bottom surface of 6) positioned over said substrate 1, wherein said lower overlayer surface is in contact with said top of said substrate 1, fig. 10, an upper overlayer surface (top surface of 6) and an intermediate overlayer 8 portion defined between said lower overlayer surface 6 and upper overlayer surface; a container region 9 within said insulating overlayer 6, container region 9 defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall, wherein all of container bottom wall is defined by an upper surface of said patterning stop region 5B, a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region (where 16 is located) defined by said charge storage lamina, wherein said contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein said contact region side walls and said contact region bottom wall are defined by a first surface of said charge storage lamina 12/13/14, and an electrical contact 16 in said

contact region, wherein respective portions of said electrical contact and said charge storage lamina occupy collectively at least a portion of said container region, fig. 10.

Regarding claim 3, Kotaki discloses a storage container structure comprising: a substrate 1 including a semiconductor structure, said substrate including a generally planar upper surface; an insulating overlayer 6 disposed over and in contact with said generally planar upper surface of said substrate 1, said insulating overlayer including a container region 9 disposed therein, said container region defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall; a patterning stop region 5B including: a lower surface substantially coplanar with generally planar upper surface of substrate 1; and an upper surface configured such that the lowermost extension of container bottom wall does not project substantially below upper surface of said patterning stop region 5B; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region (where 16 is located) defined by said charge storage lamina, wherein contact region defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein contact region side walls and contact region bottom wall are defined by a first surface of charge storage lamina 12/13/14; and an electrical contact 16 in contact region, wherein respective portions of electrical contact and charge storage lamina occupy collectively at least a portion of container region 9, fig. 10.

Regarding claim 4, Kotaki discloses a storage container structure comprising: a substrate 1 including a semiconductor structure, substrate 1 including a generally planar

upper surface, an insulating overlayer 6 disposed over and in contact with said generally planar upper surface of substrate, insulating overlayer 6 including a container region 9 disposed therein, container region defining a container cross section having container side walls, a container bottom wall, and a container interior bounded in part by container side walls and said container bottom wall; a patterning stop region 5B including: a lower surface substantially coplanar with said generally planar upper surface of said substrate, fig. 10, and an upper surface substantially coplanar with said container bottom wall; a charge storage lamina 12/13/14 over an interior surface of said container region 9; a contact region defined by charge storage lamina, wherein contact region (where 16 is located) defines a contact region cross section having contact region side walls and a contact region bottom wall, and wherein contact region side walls and contact region bottom wall are defined by a first surface of charge storage lamina; and an electrical contact 16 in contact region, wherein respective portions of electrical contact 16 and charge storage lamina 12/13/14 occupy collectively at least a portion of container region, fig. 10.

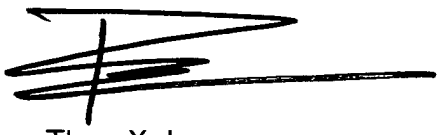
Regarding claim 5, Kotaki discloses a storage container structure according to claim 4, wherein said upper surface of patterning stop region 5B is configured such that all of container bottom wall is defined by said upper surface of said patterning stop region 5B, fig. 10.

Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Thao X. Le whose telephone number is (571) 272-1708. The examiner can normally be reached on M-F from 8:00 AM - 4:30 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M. Fahmy can be reached on (571) 272 -1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Thao X. Le
Patent Examiner
03 Mar. 2005.